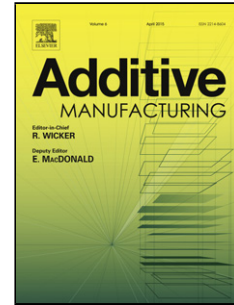


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Authors: Raghvendra P Chaudhary, Arun Jaiswal, Govind Ummethala, Suyog R Hawal, Sumit Saxena, Shobha Shukla



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**Raghendra P Chaudhary, Arun Jaiswal, Govind Ummethala, Suyog R Hawal, Sumit Saxena  
and Shobha Shukla\***

*Nanostructures Engineering and Modeling Laboratory, Department of Metallurgical Engineering and  
Materials Science, Indian Institute of Technology Bombay, Mumbai, MH, India 400076*

*\*sshukla@iitb.ac.in*

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